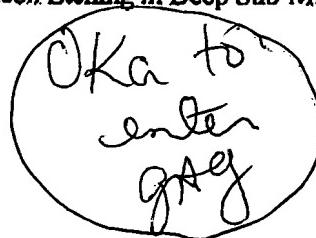


**RESPONSE UNDER 37 C.F.R. § 1.116  
EXPEDITING PROCEDURE  
EXAMINING GROUP 1700**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant: Chen, et al. Docket No.: TSM6283131RI  
Serial No.: 10/650,886 Art Unit: 1763  
Filed: August 28, 2003 Examiner: George A. Goudreau  
For: In-Situ Strip Process for Polysilicon Etching in Deep Sub-Micron  
Technology

Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450



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**RESPONSE TO FINAL OFFICE ACTION UNDER 37 CFR § 1.116**

Dear Sir:

Applicant respectfully submits the following amendment and remarks in response to the Final Office Action dated February 18, 2005. Applicant respectfully requests that this amendment and remarks be entered pursuant to the provisions of 37 CFR § 1.116, as it is believed that this amendment is fully responsive to Examiner's rejections and places the application in condition for allowance.

TSM6283131RI

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